Chapter 7.1

Plasma Etch Training Class

(etchclass)

1.0 Class Purpose

1.1 This class will prepare you to use dry-etching (plasma) systems to etch your films.

2.0 This Class is a Prerequisite for the Following Tools:

2.1 centura-3-5

2.2 centura-met

2.3 centura-mxp

2.4 ionmill6

2.5 lam6

2.6 lam7

2.7 lam8

2.8 matrix-etch

2.9 oxford-icp

2.10 oxford-rie

2.11 primaxx

2.12 semi

2.13 sts2

2.14 sts-oxide

2.15 technics-c

2.16 xetch

2.17 yes-g500

2.18 Always refer to the Prerequisite section in MercuryWeb for the most up-to-date list of prerequisites for any piece of equipment.

3.0 Training Procedure

3.1 This class provides background information for a set of tools.

3.2 Prerequisites for this class are: vacuumclass

3.3 Timeline:

3.3.1 Watch the videos (see Section 5.0).

3.3.2 Take the online exam. You may take the exam from anywhere (not just the office).

3.4 After passing the online exam, you will be automatically qualified on this class.

4.0 Reference Slides & Applicable Documents

4.1 Reference Slides Used in the Video

5.0 VideosEtch Training Workshop Video Course Part 1.mp4

5.1 Watch the following videos to get trained on this class. The videos should be watched in order. Be sure to read appendix A - Policy Addendum as well.

5.2 Video 1 - Plasma Etch Introduction

5.3 Video 2 - Reaction Chemistry

5.4 Video 3 - Choosing a Tool

5.5 Video 4 - Substrate Behavior

6.0 Appendix A - Policy Addendum for NanoLab Policies not yet covered in video format

6.1 All photoresist masks must be hard baked before entering a plasma etch tool in the NanoLab.